

1c997 U.S. PTO
10/050322

01/15/02

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10050322	FILING DATE 01/15/2002	CLASS 438	SUBCLASS 313	GAU 2812	EXAMINER <i>Barnea</i>
----------------------	---------------------------	--------------	-----------------	-------------	---------------------------

**APPLICANTS: Tsai Ming Huan; Tao Hun-Jan;
430 1756

**CONTINUING DATA VERIFIED: *none*

** FOREIGN APPLICATIONS VERIFIED: *none*

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	
Foreign priority claimed <input type="checkbox"/> yes <input checked="" type="checkbox"/> no		ATTORNEY DOCKET NO	
35 USC 119 conditions met <input type="checkbox"/> yes <input checked="" type="checkbox"/> no		67,200-613	
Verified and Acknowledged Examiners's initials <i>mm</i>			
TITLE : Bi-layer photoresist dry development and reactive ion etch method			

U.S. DEPT. OF COMM./PAT & TM-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for 0.6
Assistant Examiner		DRAWING	
		Sheets Drwg.	Figs. Drwg.
Amount Due		Print Fig.	
Date Paid			
Primary Examiner		Application Examiner	
PREPARED FOR ISSUE			
<input type="checkbox"/> TERMINAL DISCLAIMER		WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.	

FILED WITH:

☐ DISK (CRF)

☐ CD-ROM

(Attached in pocket on right inside flap)